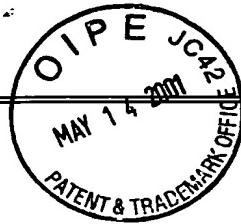


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Sheet 1 of 1

37 CFR 1.501
INFORMATION DISCLOSURE STATEMENT
IN A PATENT
(use several sheets if necessary)

Docket No.
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Applicants
Fuchs et al.

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1762

U.S. PATENT DOCUMENTS

Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If appropriate
MB	AA	3,825,763	07/23/74	Lightenberg et al.	—	—	
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
MB	AL	OS 198 52 326	11/18/99	Germany				
MB	AM	PS 195 16 450	08/08/96	Germany				
MB	AN	PS 42 19 347	05/02/96	Germany				
MB	AO	0 698 932	02/28/96	Europe				
MB	AP	0 175 578	12/27/90	Europe				
	AQ							

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

MB	AR	Vapour-Deposited CsI:Na Layers, I. Morphologic and Crystallographic Properties, Stevels et al., Philips Res. Repts. 29 (1974) pp. 340-352
MB	AS	Vapour-Deposited CsI:Na Layers, II. Screens for Application in X-ray Imaging Devices, Stevels et al., Philips Res. Repts. 29 (1974) pp. 353-362
MB	AT	Computersimulation des Photonentransports in CsI-Eingangsschirmen von Röntgenbildverstärkern, Eckenbach, Unsere Forschung in Deutschland (Philips) Vol. IV (1989) pp 51-53
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MB	AV	Evolutionary Selection, A Principle Governing Growth Orientation in Vapour-Deposited Layers, van der Drift, Philips Res. Repts. Vol. 22 (1967) pp. 267-268
	AW	
	AX	
	AY	
	AZ	

Examiner <i>M.J. Chal</i>	Date Considered <i>9/18/02 7/13/03</i>
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.